



9/18/02  
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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

**Shinji Mizutani, et al.**

Serial No.: **09/930,310**

Group Art Unit: **1756**

Filed: **August 16, 2001**

Examiner: **Stephen Rosasco**

For: **MICRO DEVICES MANUFACTURING ...**

Attorney Docket: **950455D**

**AMENDMENT**

**RECEIVED**

SEP 18 2002

**TC 1700**

Commissioner for Patents  
Washington, D.C. 20231

Date: **September 17, 2002**

Sir:

In response to the Office Action mailed on April 17, 2002, payment for two months' extension of time being attached, please amend the above-identified application as follows:

**IN THE CLAIMS**

1. 6. (Amended) A mask formed with an original pattern of alignment mark together with a pattern to be transferred, wherein the original pattern of said alignment mark is formed by disposing, between adjacent bright portions having a width of not less than a predetermined value, one or more bright patterns having a width of less than said predetermined value with a pitch less than said predetermined value.

2. 7. (Amended) A mask according to claim 6, wherein the maximum value of said pitch is determined so that a concave and convex pattern formed by transferring said bright pattern on said mask onto a substrate is not more than resolution of an alignment sensor.

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